

FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. SITECH.004A	APPLICATION NO. 09/974,725
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT  FEB 08 2007  (USE SEVERAL SHEETS IF NECESSARY)	APPLICANTS Wang, et al.	
	FILING DATE October 9, 2001	GROUP 12
COPY OF PAPERS ORIGINALLY FILED		

## **U.S. PATENT DOCUMENTS**

**RECEIVED**

FEB 13 2002

TC 1700

## **FOREIGN PATENT DOCUMENTS**

**EXAMINER  
INITIAL**

**OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)**

RSP

Kirkbir, et al., "Parametric study of strength of silica gels," Journal Non-Crystalline Solids, Vol. 178, p. 284-292 (1994).

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EXAMINER	LOVERING	DATE CONSIDERED	8-5-03
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.			

FORM PTO-1449  O/P/E SC144 FEB 04 2002 PATENT & TRADEMARK OFFICE	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (USE SEVERAL SHEETS IF NECESSARY)	ATTY. DOCKET NO. SITECH.004A	APPLICATION NO. 09/974,725
		APPLICANT Unnamed	<i>RECEIVED</i> FEB 08 2002 TC 1700
		FILING DATE October 9, 2001	GROUP <i>Holmberg 1112</i>

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
<i>RDL</i>	4,851,373	02/25/1989	Hench, et al.	501	12	
	5,023,208	06/11/1991	Pope, et al.	501	12	
	5,071,674	12/10/1991	Nogues, et al.	427	57	
	5,076,980	12/31/1991	Nogues, et al.	264	65	
	5,196,382	03/23/1993	Hench, et al.	501	12	
	5,243,769	09/14/1993	Wang, et al.	34	27	
	5,264,197	11/23/1993	Wang, et al.	423	330	
<i>RDL</i>	5,343,633	09/06/1994	Wang, et al.	34	92	

## FOREIGN PATENT DOCUMENTS

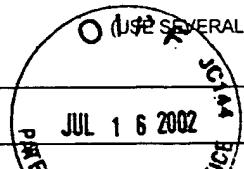
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
<i>RDL</i>	Murata, Hideaki, et al., <u>Drying and sintering of large SiO<sub>2</sub> monoliths</u> , SPIE, Vol. 2288 Sol-Gel Optics III, pp. 709-716 (1994).

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RJL	2,092,163	09/07/1937	Johnson	—	—	
	2,441,422	05/11/1948	Krieble, et al.	—	—	
	2,794,002	05/28/1957	Haensel, et al.	—	—	
	3,850,971	11/26/1974	Termin, et al.	—	—	
	4,104,363	08/01/1978	Vozka, et al.	103	338	
	4,477,580	10/16/1984	Fleming, Jr.	501	338	
	4,752,459	06/21/1988	Pepper	501	338	
	4,810,674	03/07/1989	Che, et al.	501	2002	
	5,023,208	06/11/1991	Pope, et al.	501	2002	
	5,380,510	01/10/1995	Matsui, et al.	423	338	
RJL	5,895,770	04/20/1999	Pullukat, et al.	502	103	

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
RJL	JP 59-30730 A	02/18/1984	Japan (Abstract)	423	338		
RJL	PCT/US02/02707	06/25/2002	Patent Cooperation Treaty (PCT) Search Report	—	—		

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
RJL	Brinker & Scherer, "Sol-Gel Science, The Physics and Chemistry of Sol-Gel Processing," Academic Press, 1990 pp. 483-498.

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<p>FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE</p> <p><b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b></p> <p>(USE SEVERAL SHEETS IF NECESSARY)</p>	<p>ATTY. DOCKET NO. SITECH.004A</p> <p>APPLICANTS Wang, et al.</p> <p>FILING DATE October 9, 2001</p>	<p>APPLICATION NO. 09/974,725</p> <p>GROUP <u>12</u></p>
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## **U.S. PATENT DOCUMENTS**

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EXAMINER L. OVERING

**DATE CONSIDERED**

8-5-03

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